



**THE 11TH TECHNICAL & SCIENTIFIC MEETING OF ARCSIS
CALL FOR PAPERS
STUniversity, Fuveau, France - 20 & 21 November 2008**

For eleven years now, the **Technical & Scientific Meeting of ARCSIS** has brought together Semiconductor manufacturers, equipment and materials suppliers and research centers on leading-edge topics related to microelectronics in response to the market's requirements. **This 11th Meeting** will be dedicated to **"Wafer Manufacturing Process Control: methods, applications and new challenges"** and will take place on **20 & 21 November 2008** at STUniversity in Fuveau, (France). **English** will be used for all conferences and documents.

Objectives:

This meeting will be the opportunity for the scientific community, for IC manufacturers and suppliers involved in the topic:

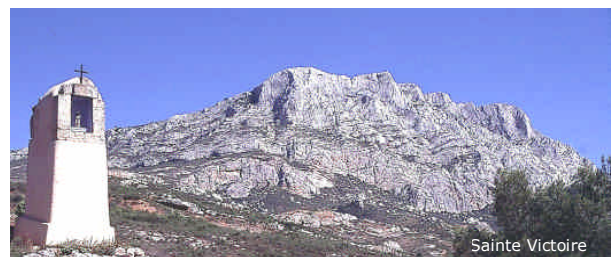
- to be informed of the latest technical developments and challenges,
- to optimize the technological supply and demand,
- to share information and discuss the latest development results in an informal atmosphere,
- to open new prospects for partnership.

These two days will consist of **scientific and technical conferences and posters** presented by local and worldwide experts from research centers and industry.

Location of the event:

This Meeting will be held at STUniversity in Fuveau at the foot of the "Sainte Victoire" mountain in Provence, in the heart of one of the major poles of microelectronics in France. The STU campus is fully equipped with the standard Audio/Video media systems required for presentations.

The event will take place at 20km from Aix en Provence, city of art and culture, well-known for its architectural beauty. Landscapes are dominated by the "Sainte Victoire" mountain painted by the famous artist from Aix, Paul Cezanne. But it is also an ideal base for visiting the rest of Provence and its beautiful countryside all within a few kilometres: the Calanques, Camargue, the Luberon and the Riviera. For further information about Provence: www.aixenprovencetourism.com



CALL FOR PAPERS

“Wafer Manufacturing Process Control: methods, applications and new challenges”

The presentations will be about methodologies or actions put in place to correct or avoid in-line process control weaknesses or failures in the following domains:

Methodology and methods:

- **Measurement - sampling**
- **Uniformity monitoring**
- **R to R – Fault Detection and Classification (FDC)**
- **SPC – AEC – APC**

Applications:

- **Materials monitoring : raw silicon, oxide, metal, other layers**
- **CD, overlay, resistivity, thickness ...**
- **Parametric testing (PCMs)**
- **EWS (Electrical product Wafer Sort)**
- **Oxide integrity, charging**
- **Defectivity, silicon defects**
- **New materials characterisations**
- **Wafer edge control, cleaning**
- **Fluids monitoring : air, water, gases, chemicals**

New challenges:

- **Process control adapted to zero ppm reject level driven by automotive market**
- **Others**

Authors, whether they are equipment manufacturers, suppliers or users are strongly encouraged to highlight actual case studies in their presentation. Joint presentations by suppliers and users will be appreciated.

Instructions for abstracts:

Abstracts to be considered for presentation (20mn) must include one page of text with a title, the authors' names, their affiliation and a summary in three parts:

- 1) Context / Study motivation
- 2) Description of approach and techniques
- 3) Results / Conclusions / Perspectives

An additional page can be added with illustrations. **Deadline for abstract submission is Monday 16th June 2008.** Authors will be notified of acceptance of their papers by 9th July 2008.

Proceedings

Publication of a Proceedings Volume is planned. All authors accepted for their presentation will be required to submit a Proceedings Volume manuscript **on Friday 31st October 2008 at the latest.** Proceedings will then be made available to attendees at the meeting.

Contact for submission of abstracts / Information

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